

10/3/03

H/C/Ampt

Customer No.: 31561
 Application No.: 10/064,208
 Docket No.: 8309-US-PA

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:)
 CHEN)
)
 Serial No. : 10/064,208)
 Filed : 06/21/2002)
 For : SUBSTRATE EXPOSURE)
 APPARATUS AND METHOD)

Examiner : Christopher G. Young
 Art Unit : 1756
 Docket No. : 8309-US-PA

No fee is believed to be due. However, the Commissioner is authorized to charge any fees required in connection with the filing of this paper to account No. 50-2620 (Order No. 8309-US-PA).

AMENDMENTS AND RESPONSE TO OFFICE ACTION

U.S. Patent and Trademark Office
 Commissioner for Patents
 2011 South Clark Place
 Customer Window, Mail Stop Non-Fee Amendment
 Crystal Plaza Two, Lobby, Room 1B03
 Arlington, Virginia 22202

Dear Sir:

In reply to the Office Action dated June 26, 2003, Applicants submit the following Amendments and Remarks.

10/06/2003 CS1AS1 00000006 502620
 01 FC:1202 198.00 DA

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AMENDMENTS

Please amend the application as indicated hereafter.

In the Claims:

1 (withdrawn). A substrate exposure apparatus, applicable to transfer a pattern to a photoresist on a surface of a substrate, the substrate exposure apparatus comprising:

a scan light source, disposed at a position spaced from a surface of the photoresist on the substrate with a distance, and the scan light source comprising a plurality of point light sources; and

a scan control system, converting the pattern into a timing signal to control light and dark status of each of the point light sources at different times, the scan control system further allows the substrate exposure apparatus to have a scan function, such that the scan light source scans the photoresist at least once along a scan path for exposure.

2 (withdrawn). The substrate exposure apparatus according to claim 1, wherein the substrate includes a printed circuit board.

3 (withdrawn). The substrate exposure apparatus according to claim 1, wherein the substrate includes a wafer.

4 (withdrawn). The substrate exposure apparatus according to claim 1, wherein the substrate includes various types of package substrates.

5 (withdrawn). The substrate exposure apparatus according to claim 1, wherein the point light sources are arranged into one line light source.